

## Reference number list

1 substrate  
2 well area  
5 3 buried layer  
4 epitaxial layer  
5 isolation area  
6 connection well  
7 oxide layer  
10 8 nitride layer  
9 conductive electrode layer  
10 photoresist mask  
11 terminal layer  
12 well  
15 13 conductive layer  
14 gate dielectric layer  
15 first gate electrode layer  
16 base area  
17 collector area  
20 18 well  
19 conductive layer  
20 highly conductive layer  
20a diffusion layer  
21a TEOS isolation layer  
25 21b nitride isolation layer  
22 second isolation layer  
23a ARC layer  
23b ARC layer  
24 photoresist  
30 25 photoresist  
26 isolation layer  
27 NPN base area  
28 NPN collector area  
29 LDD area  
35 30 first spacing layer  
31 second spacing layer  
32 HDD area  
33 terminal layer

33a diffusion area  
34 protective layer  
35 photoresist mask  
36 silicon layer